

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|--|---|------------------|---------|------------------|
| L1 | 3 | (mask and substrate and (mating or mated)).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/29 16:04 |
| L2 | 57 | (mask and substrate and (contacting)).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/29 16:04 |
| L3 | 23 | ((depositing or forming) and mask\$3). clm. and ((multilayer or multi-layer) near2 (three-dimensional)).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/29 16:06 |
| S1 | 232 | ((cohen near2 adam) (dennis near2 smalley)).in. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:06 |
| S3 | 36 | ((cohen near2 adam) (dennis near2 smalley)).in. and (depositing and mask\$3).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:55 |
| S4 | 978 | (216/2).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/11/26 13:20 |
| S6 | 44 | (216/43).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:50 |
| S7 | 14279 | (depositing or forming).clm. and (multilayer or multi-layer) near2 (mems or micromechanical or microstructure\$1 or microelectromechanical or structure) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/11/30 17:20 |
| S8 | 2419 | (depositing or forming).clm. and (multilayer or multi-layer) near2 (mems or micromechanical or microstructure\$1 or microelectromechanical or structure)). clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/11/26 13:38 |

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| S9 | 868 | (depositing or forming and mask\$3). clm. and ((multilayer or multi-layer) near2 (mems or micromechanical or microstructure\$1 or microelectromechanical or structure)). clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/11/26 13:38 |
| S10 | 411 | ((depositing or forming) and mask\$3). clm. and ((multilayer or multi-layer) near2 (mems or micromechanical or microstructure\$1 or microelectromechanical or structure)). clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/29 16:06 |
| S11 | 4 | ((("5493096") or ("6183064"))).PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/11/27 20:05 |
| S12 | 322 | (depositing or forming).clm. and (mask\$3 near5 curvature) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:02 |
| S13 | 330 | (depositing or forming).clm. and (contact adj mask\$3).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:02 |
| S14 | 346 | (depositing or forming or etching).clm. and (contact adj mask\$3).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:02 |
| S15 | 6 | (depositing or forming or etching).clm. and (contact adj mask\$3).clm. and curvature | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:03 |
| S16 | 6 | (depositing or forming or etching).clm. and (contact adj mask\$3).clm. and (curvature or convex or concave or curved).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:05 |
| S17 | 208 | (118/721).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:17 |

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| S18 | 34 | S17 and (curvature or convex or concave or curved) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:08 |
| S19 | 361 | flexible adj mask | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/24 13:55 |
| S20 | 1459 | deposition adj mask | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:25 |
| S21 | 157 | (deposition adj mask).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:28 |
| S22 | 3 | (mask and substrate and mating).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/29 16:02 |
| S23 | 4 | (mask\$1 and substrate\$1 and mating).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2005/12/09 17:30 |
| S24 | 724 | contact adj mask and (curvature or convex or concave or curved) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 15:53 |
| S25 | 267 | deposition adj mask and (curvature or convex or concave or curved) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:24 |
| S26 | 1397 | (216/41).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:32 |
| S27 | 46 | (216/43).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:25 |

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| S28 | 34 | (216/45).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:25 |
| S29 | 43 | (156/345.19).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:32 |
| S30 | 101 | (156/345.3).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:32 |
| S31 | 74 | (smalley and cohen).in. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/11 13:52 |
| S32 | 34 | 156/dig.19.ccls. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 15:53 |
| S33 | 81 | 156/dig.20.ccls. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 15:53 |
| S34 | 774 | ((contact or deposition) adj2 mask) and (electrochemical or electrodeposit\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:48 |
| S35 | 116 | ((contact or deposition) adj2 mask) and (electrochemical or electrodeposit\$4).ab. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:01 |
| S36 | 168 | ((contact or deposition) adj2 mask) and (electrochemical or electrodeposit\$4).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:11 |
| S37 | 2 | ("6027630").PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:38 |

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| S38 | 136 | (instant adj mask\$3) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:38 |
| S39 | 34 | (216/45).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:50 |
| S40 | 5 | ((cohen near2 adam) (dennis near2 smalley)).in. and ((mating or mated) and mask\$3).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:56 |
| S41 | 483 | ((mating or mated) and mask\$3).clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 16:57 |
| S42 | 246 | ((mating or mated) and mask\$3).clm. and (electrochemical or deposit\$4 or etching) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 17:11 |
| S43 | 1 | ("4388388").PN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/06/27 17:10 |
| S44 | 100 | (pre-patterned near2 mask\$3) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 16:37 |
| S45 | 240 | (205/666).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 17:58 |
| S46 | 306 | (205/206).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/27 17:58 |
| S47 | 2 | ("6027630").PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:06 |

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| S48 | 303 | (205/135).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:38 |
| S49 | 7 | ((pressed or pressing) adj2 mask).clm. and (electroless or plating or electrochemical or electrodeposit\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:49 |
| S50 | 19 | ((pressed or pressing) near3 mask). clm. and (electroless or plating or electrochemical or electrodeposit\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:51 |
| S51 | 20 | ((pressed or press-fit\$3 or pressing) near3 mask).clm. and (electroless or electrolytic or plating or electrochemical or electrodeposit\$4) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:02 |
| S52 | 240 | (205/666).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 12:59 |
| S53 | 82 | (205/667).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:00 |
| S55 | 108 | ((pressed or press-fit\$3 or pressing) near3 mask) and (electroless or electrolytic or plating or electrochemical or electrodeposit\$4). clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:02 |
| S56 | 2 | ((pressed or press-fit\$3 or pressing) near3 mask) with bath and (electroless or electrolytic or plating or electrochemical or electrodeposit\$4). clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:02 |
| S57 | 3 | ((pressed or press-fit\$3 or pressing) near3 mask) with bath | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:03 |
| S58 | 7 | ((pressed or press-fit\$3 or pressing) near3 mask) with (bath or electrolyte) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/06/28 13:03 |

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| S59 | 345 | ((contact or adhesive) adj mask) and electrochemical | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 15:57 |
| S60 | 64 | ((contact or adhesive) adj mask) and electrochemical and (bubbles or (air adj pockets)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 15:54 |
| S61 | 1427 | (216/41).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 15:59 |
| S62 | 152 | ((etching or plating) near2 mask\$3).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 16:59 |
| S63 | 284 | (118/406).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 16:41 |
| S64 | 0 | ((electrochemical or electrolytic) near2 mask\$3).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:16 |
| S65 | 0 | ((electrochemical or electrolytic) near3 mask\$3).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 16:59 |
| S66 | 32 | ((electrochemical or electrolytic) near3 mask\$3).ab. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:00 |
| S67 | 55 | ((cohen near2 adam) (dennis near2 smalley)).in. and depositing.clm. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 17:05 |
| S68 | 137 | ((electrochemical or electrolytic) and (micromechanical or microelectromechanical or microstructure\$1 or MEMS or multilayer)).ab. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:08 |
| S69 | 57 | ((electrochemical or electrolytic) and (micromechanical or microelectromechanical or microstructure\$1 or MEMS)).ab. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:08 |

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| S70 | 36 | ((mating or mated) and mask\$3).clm. and (electrochemical or electrolytic) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 17:15 |
| S71 | 8 | ((electroplating) near2 mask\$3).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:17 |
| S72 | 26 | ((adhesive) near2 mask\$3).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:19 |
| S73 | 63 | ((adhesive) near3 mask\$3) with (plating or electroplating) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:23 |
| S74 | 12 | ((soft) near3 mask\$3) with (plating or electroplating) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:28 |
| S75 | 8692 | mask\$3 with (plating or electroplating) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:29 |
| S76 | 529 | (mask\$3 with (plating or electroplating)).ab. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:29 |
| S77 | 55 | (mask\$3 with (plating or electroplating)).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/14 17:35 |
| S78 | 13 | ((("4126521") or ("3527679") or ("4294681")).PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/14 17:35 |
| S79 | 14 | (flexible adj2 mask) with (etching or plating or electroplat\$3) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/17 16:05 |
| S80 | 124 | (flexible adj2 mask) and (etching or plating or electroplat\$3) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/17 15:38 |
| S81 | 59 | (flexible adj2 mask) with (fluid or pressure or vacuum) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/17 16:08 |
| S82 | 18 | (flexible adj2 mask) with (adhesive) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/17 16:08 |
| S83 | 385 | (flatten with vacuum) | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:19 |

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| S84 | 12 | (flatten with vacuum) and (holder or chuck).ti. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:16 |
| S85 | 57 | (flatten with vacuum) and mask | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:19 |
| S86 | 171 | (flatten\$3 with vacuum) and mask | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:32 |
| S87 | 11 | (flatten\$3 with vacuum) with mask | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:19 |
| S88 | 406 | flatten\$3 near3 mask | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:39 |
| S89 | 135 | (curvature near3 mask).clm. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:44 |
| S90 | 148 | (\$7plating near3 mask).ab. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/18 16:45 |
| S91 | 606 | (\$7plating near3 mask).ab. | JPO | OR | OFF | 2006/07/18 16:46 |
| S92 | 1084 | (\$7plating near3 mask).ab. | JPO; DERWENT | OR | OFF | 2006/07/18 16:45 |
| S93 | 6 | (\$7plating and curvature and mask).ab. | JPO | OR | OFF | 2006/07/18 17:22 |
| S94 | 2 | ("4388388").PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/18 17:22 |
| S95 | 1889 | (156/285).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 10:58 |
| S96 | 428 | (156/87).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 10:57 |
| S98 | 100 | S95 and mask\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 10:58 |

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| S99 | 105 | S95 and (mask\$3 or stencil) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 14:29 |
| S10 0 | 46 | S95 and S96 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 11:14 |
| S10 1 | 1 | ("4127436").PN. | US-PGPUB; USPAT; USOCR | OR | OFF | 2006/07/19 11:16 |
| S10 2 | 76 | ((plating or electroplating) and curved).ti. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 14:29 |
| S10 3 | 428 | (156/87).CCLS. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 14:54 |
| S10 4 | 3 | ((("7073223") or ("20050182372"))).PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/19 14:55 |
| S10 5 | 7 | ((("6564030") or ("5670202") or ("6136141"))).PN. | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/21 15:12 |
| S10 8 | 198 | (cc or conformable) adj mask | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/07/24 13:55 |